

**IN THE CLAIMS:**

Please amend the claims as follows:

Please insert the following after the section heading "CLAIMS.": What is claimed is:

1. (CURRENTLY AMENDED) A wafer rotating device comprising:
  - at least three rollers rotatably provided about axes arranged at parallel intervals and which rotate over ~~at the~~ circumferential surface of a disk-shaped wafer;
  - a rotation drive mechanism that rotates and drives at least one of the rollers;
  - an interval adjustment mechanism capable of adjusting ~~the~~ dimensions of the intervals of the rollers; and[[,]]
  - a load control device that controls ~~at the~~ load applied from the rollers to the wafer in ~~at the~~ radial direction of the wafer when the wafer is clamped between the rollers.
2. (CURRENTLY AMENDED) ~~The~~A wafer rotating device according to claim 1 wherein[[,]] a load cell is provided in the interval adjustment mechanism that detects the load applied to the rollers along ~~at the~~ direction of movement of the rollers, whereinand the load control device controls the interval adjustment mechanism so that the load detected by the load cell is maintained constant.
3. (CURRENTLY AMENDED) ~~The~~A wafer rotating device according to claim 1 wherein, in addition to the rollers ~~are being~~ rotatably provided around the axes which ~~are~~ arranged roughly in ~~at the~~ vertical direction, ~~and the rollers include a flange section and a circumferential surface, wherein the flange section has having a diameter larger than the circumferential surface of the rollers, and the flange section is provided below the circumferential surface which that~~ clamps the wafer, and the flange section has an inclined surface in which ~~at the~~ upper surface of the flange section gradually becomes lower moving towards ~~at the~~ outside in ~~at the~~ radial direction.

4. (CURRENTLY AMENDED) ~~The~~A wafer rotating device according to claim 1 wherein;  
~~the interval an angle between the other two of the rollers adjacent to one of the rollers and roller~~  
on both sides ~~of the one of the rollers~~ is smaller than 180°.
5. (CURRENTLY AMENDED) ~~The~~A wafer rotating device according to claim 4  
wherein[[,]] pairs of rollers are arranged at three ~~or more locations or more~~ at intervals in ~~at the~~  
circumferential direction of ~~the~~a wafer.
6. (CURRENTLY AMENDED) An edge flaw inspection device comprising:  
a wafer rotating device ~~including according to claim 1;~~  
at least three rollers rotatably provided about axes arranged at parallel intervals  
and which rotate over a circumferential surface of a disk-shaped wafer,  
a rotation drive mechanism that rotates and drives at least one of the rollers;  
an interval adjustment mechanism capable of adjusting dimensions of the  
intervals of the rollers, and  
a load control device controls that controls a load applied from the rollers to the  
wafer in a radial direction of the wafer when the wafer is clamped between the rollers,  
a light source that radiates light onto the circumferential surface of a wafer supported by  
the wafer rotating device; and[[,]]  
a light detector that detects light that has been radiated from the light source which is  
reflected on the circumferential surface of the wafer.